

ナノメートル計測学 システム創成学科BISコース

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東京大学工学系研究科精密機械工学専攻
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精密設計の基本概念

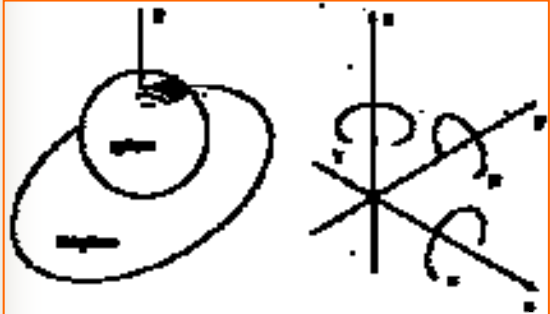
Fundamental Concepts in Precision Design

- Does it contain the correct number of **kinematic constraints**?
- Where are the **metrology and force loops** and how are they shared?
- Are there any **heat sources** and, if so, what are their likely effects?
- Is the design symmetrical and are the **alignment principles** obeyed?
- What other source of error are likely to be encountered and can they be reduced by using **compensation or nulling**?

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Basic point constraints

- A single degree of freedom constraint provided by a sphere on a flat. The freedoms of the Cartesian coordinate system are also shown.



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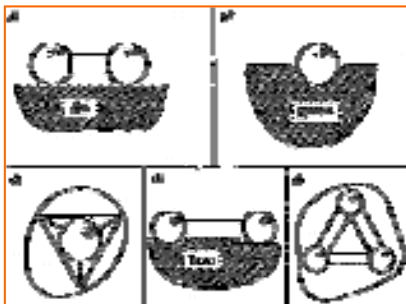
Two lemmas

- Any unconstrained rigid body has six degrees of freedom.
- The number of contact points between any two perfectly rigid bodies is equal to the number of their mutual constraints.
- 制約されていない剛体は6自由度を持つ。X, Y, Z方向の平行移動, X軸, Y軸, Z軸周りの回転。
- 2つの剛体間の接触点の数が制約の数と等しい。自由度は, 6 - 制約の数

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Number of contact points

- Idealized kinematic constraints
 - two balls rigidly connected and resting on a flat
 - a ball in a vee groove
 - a single ball in a trihedral hole
 - two balls rigid by attached with one resting in a groove and the other on a flat
 - three rigidly attached balls on a flat



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Trihedral contacts

- Methods for achieving trihedral contacts

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Idealized constraint geometries

- Idealized constraint geometries for the contact of rigidly connected spheres on a combination of flats, grooves and trihedral holes

Constraints	Configuration
1	Ball on flat
2	Link on flat Ball in groove
3	Ball in trihedral hole Link with one ball in groove and the other on a flat Three links of balls suitably distributed on a flat
4	Link with one ball in trihedral hole and the other on a flat Link with two balls both in a vee groove Link of three balls with two on a flat and one in a groove Link of four balls suitably distributed on two inclined flats
5	Link of two balls with one in a trihedral hole and the other in a vee groove Link of three balls with two in vee grooves and one on a flat Link of four balls with one in a vee groove and three on a flat Link of five balls suitably distributed on two inclined flats

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Single degree of freedom movement

- A single degree of freedom movement consisting of five point contacts on a straight prismatic vee slide

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Screw and diameter measuring instrument

- schematic diagram representing two orthogonal views of a screw and diameter measuring instrument

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Kinematic clamps

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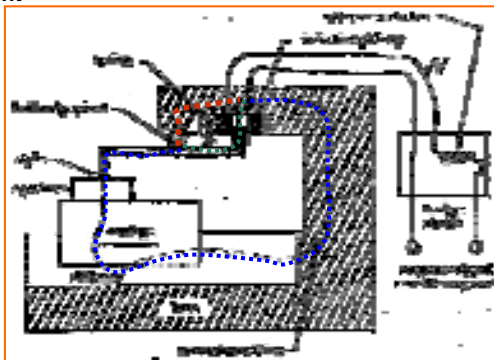
Rotary motion

- Kinematic representation of a system having five constraints
- A variety of rolling element bearings and their respective freedom axes

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Measurement and force loop

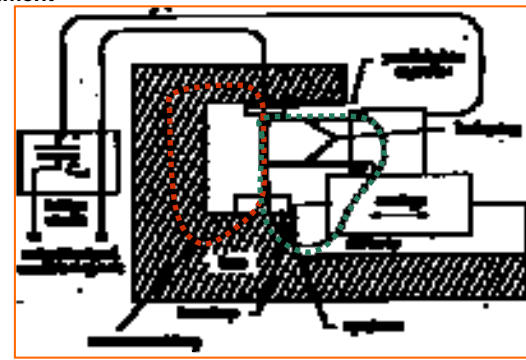
- Schematic diagram of a simple surface measuring instrument



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Simple surface measuring instrument

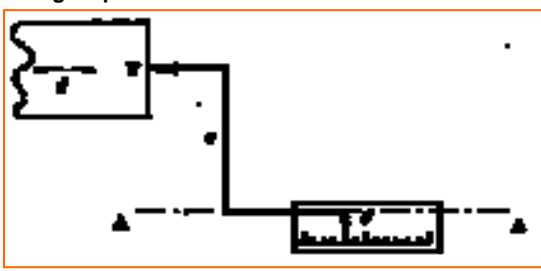
- An alternative design for the simple surface measuring instrument



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Abbe offset

- Measuring displacement with an Abbe offset



$$S_{\theta} = \frac{d_0(1 - \cos \theta)}{\cos \theta} - a \sin \theta$$

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アッペ式測長機


- ULM600 (ドイツ ツァイス社)
 - 測定範囲: 外側測定 0 ~ 600 mm
 - 内側測定 1 ~ 460 mm
 - 測定システム: 分解能 0.05 μm
 - 測定精度: 比較測定 0.15 μm
 - 直接測定 (0.2 + L mm / 1000) μm



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Abbe's Principle

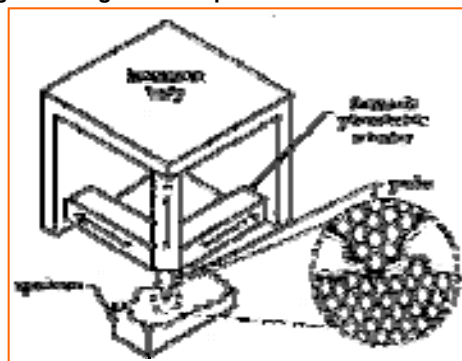
- When measuring the displacement of a specified point, it is not sufficient to have the axis of the probe parallel to the direction of motion, the axis should also be aligned with (pass through) the point.
- Ernst Abbe, 1840 - 1905 founder of the Carl Zeiss



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Nulling

- Scanning tunneling microscope



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Mechanical compensation

- Examples of constant frequency oscillators for clocks and watches; a) constant inertia, b) constant length

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Piezoelectric actuator

- Piezoelectric actuator with inbuilt capacitance position sensing (reproduced with kind permission of Queensgate Instruments)

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Reversal Method (反転法)

- Error inversion method

$$S_1(x) = R(x) + t(x)$$

$$S_2(x) = R(x) - t(x)$$

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Nanohardness instrument

- Schematic representation of proposed nanohardness instrument. The hatched sections carry the high stability

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Abbe Principle

- An alternative layout for the instrument, better complying with the Abbe principle

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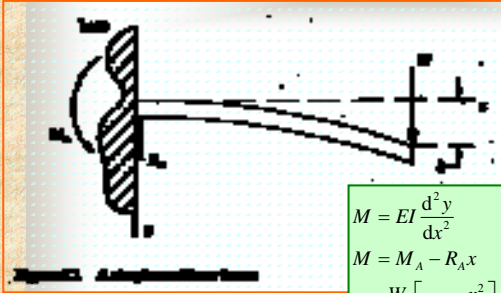
弾性ヒンジ

Flexure Design for Positioning and Control

- A simple flexure design
- The pros and cons of flexure design
 - The advantages of flexures
 - The disadvantages of flexures
- Linear spring mechanisms
 - Simple and compound leaf spring mechanisms
 - Notch type spring mechanisms
 - Kinematic analysis of linear spring mechanisms
 - Additional considerations with compound spring designs
- Angular motion flexures
- Dynamic characteristics of flexure mechanisms
- Case studies
 - X-ray interferometry
 - The measurement of friction between a diamond stylus and specimen

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A Simple Cantilever Beam



$$M = EI \frac{d^2 y}{dx^2}$$

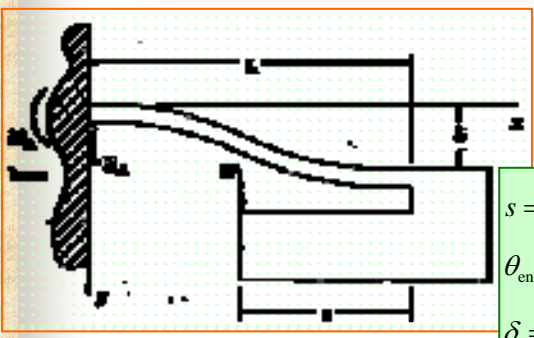
$$M = M_A - R_A x$$

$$\theta = \frac{W}{EI} \left[Lx - \frac{x^2}{2} \right]; \quad \theta_{\text{end}} = \frac{WL^2}{2EI}$$

$$y = \frac{W}{EI} \left[\frac{Lx^2}{2} - \frac{x^3}{6} \right]; \quad \delta = \frac{WL^3}{3EI}$$

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Deflection of a cantilever beam



$$s = \frac{L}{2}$$

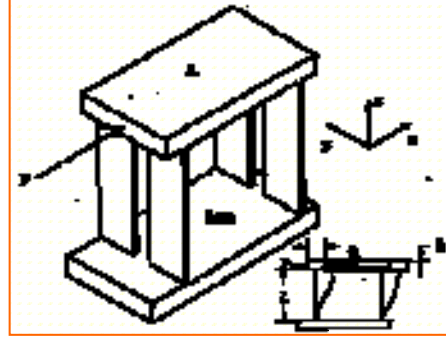
$$\theta_{\text{end}} = 0$$

$$\delta = \frac{WL^3}{12EI}$$

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Simple leaf type linear spring

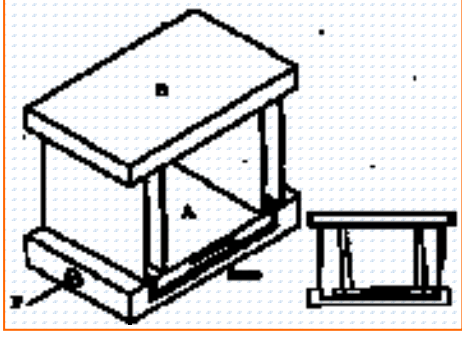
- Simple leaf type linear spring; schematic representation of flexure distortion shown in side view



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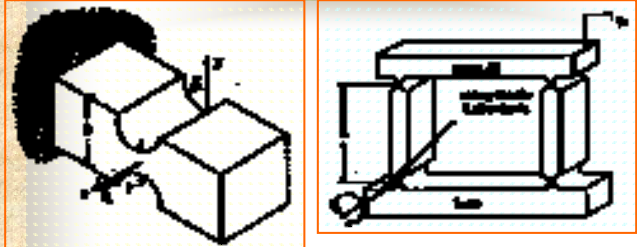
Compound linear spring

- Compound linear spring; schematic representation of the mode of distortion



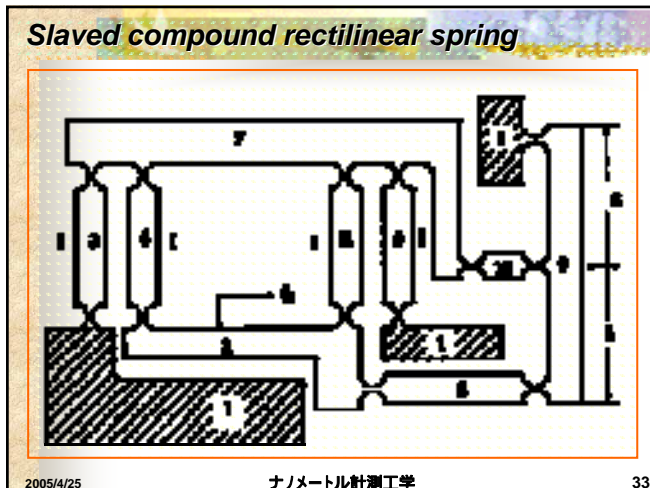
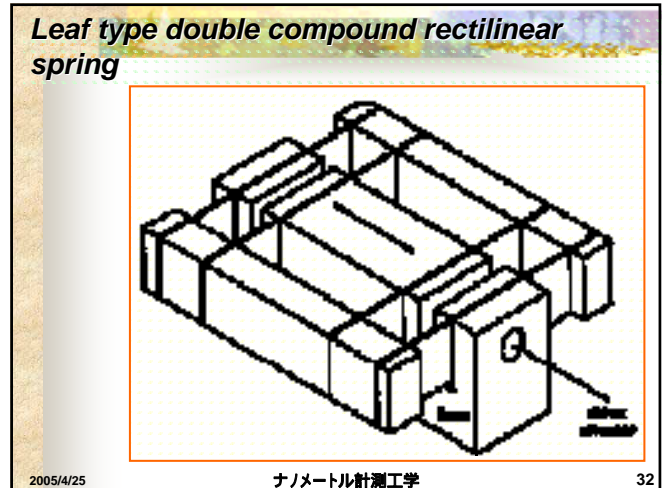
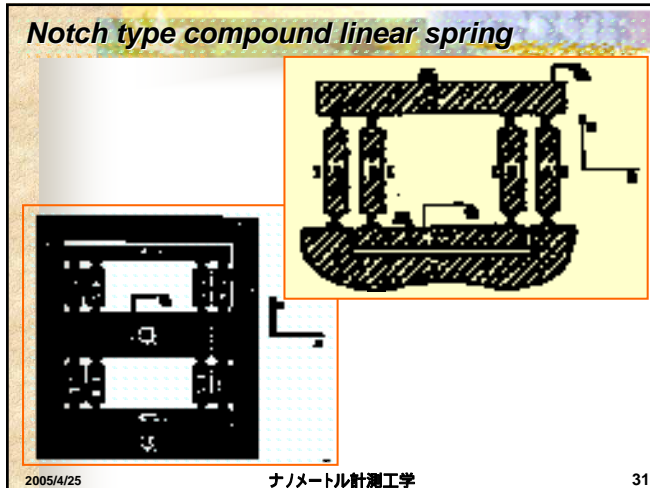
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Notch hinge



$$\theta_z = \frac{9\pi R^{1/2} M}{2Ebt^{5/2}} \approx \frac{9KRM}{EI} \approx \frac{24KRM}{Ebt^3}$$

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- Advantages of flexures**
- They are wear free.
 - Flexures can be manufactured from a single piece of material.
 - Displacements are smooth and continuous at all levels.
 - Insensitive to bulk temperature changes and to temperature gradients in some planes
 - Displacements can be accurately predicted.
 - Failure mechanisms due to fatigue or overloading can be easily detected.
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- Disadvantages of flexures**
- The force for a given deflection is dependent upon the elastic modulus of the flexure.
 - There will be hysteresis due to dislocation movement in most materials.
 - Flexures are restricted to small displacements.
 - Out of plane stiffness tends to be relatively low.
 - They cannot tolerate large loads.
 - Unless precautions are taken, accidental overloads can lead to fatigue.
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ナノメートル計測のトレーサビリティ

A decorative horizontal bar with a floral pattern, likely serving as a section separator or a visual element in a presentation.

Traceable Nanometrology

- Advances in traceable nanometrology at the National Physical Laboratory
- NPL (www.npl.co.uk) 1900年に設立
 - The National Physical Laboratory is the United Kingdom's national standards laboratory. From the supermarket to the hospital, from manufacturing to information technology, accurate measurement is essential to a civilised way of life. The work of the NPL as the UK authority for physical measurement standards and metrology (the science of measurement) is therefore vital to us all.

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対応する計測機器

- 4種類の測定機
 - NanoSurf IV
 - Metrological AFM
 - Combined optical and x-ray interferometer (COXI)
 - Small-scale CMM

Figure 1. Range of the instruments used at NPL (the scale is in metres).

- 現実には多くのGapが存在する。
 - SXMとCMM
 - 2.5Dと3D

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NanoSurf IV

- 表面測定機にレーザ測長を付加した
 - X軸, Z軸の不確かさ 1.3 nm

Figure 2. Schematic diagram of NanoSurf IV.

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Metrological AFM

- AFMにレーザ測長を不可した
 - 6 DOFの測長

Figure 3. Micrographical AFM image of a step-etched sample. The image is 50 um square and the vertical height of the step is 254 nm.

Figure 4. Head and target mirror configuration of the metrological AFM.

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COXI

- X線干渉と光干渉を組合わせた。
 - X線: 0.192 nm
 - 光: 633 nm

Figure 6. Schematic diagram of the COXI system (University of Royal Society of London).

Figure 7. Interferogram showing a series of vertical lines.

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Small-scale CMM

- SCMM
 - CMMの上に組み込んでい
 - 50 mm x 50 mm x 50 mm の測定範囲で、不確かさ 50 nm
 - 6本のレーザを使い、3つの鏡の6DOFを測定する
 - 定接触力(0.1 mN)のプローブ

Figure 8. Schematic diagram of the SCMM.

Figure 9. Probe assembly of the SCMM showing transducers and bearings.

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